



Session Title:	[TE2] EUV Resist & Advanced Lithography for Optical Materials
Session Date:	November 21 (Tue.), 2023
Session Time:	10:30-12:10
Session Room:	Room E (Sidney Room, 2F)
Session Chair:	Prof. Myung-Gil Kim (Sungkyunkwan Univ., Korea)

[TE2-1] 10:30-10:50

Mask Shift Double Exposure in ArF Immersion Lithography

Jungchul Song, Gyu-Won Han (Nat'l NanoFab Center, Korea), Jeonghwan Kim (SK Materials Performance, Korea), and Ga-Won Lee (Chungnam Nat'l Univ., Korea)

[TE2-2] [Invited] 10:50-11:20

Recent Advances in Inorganic EUV Photoresist

Yeo Kyung Kang, Sun Jin Lee (Sungkyunkwan Univ., Korea), Chan-Cuk Hwang (Pohang Accelerator Lab., Korea), and Myung-Gil Kim (Sungkyunkwan Univ., Korea)

[TE2-3] 11:20-11:40

Electron Beam Cross-Linking Mechanism of Cyclotetrasiloxane-Based Inorganic Molecular Resists for EUV Lithography

Jiyoung Bang, Hyeok Yun, Wonchul Kee (Chonnam Nat'l Univ., Korea), Sunyoung Lee (Sungkyunkwan Univ., Korea), and Hyun-Dam Jeong (Chonnam Nat'l Univ., Korea)

[TE2-4] [Invited] 11:40-12:10

Low-Cost and Scalable Manufacturing of Optical Metasurfaces in the Visible Using Engineered Optical Materials (PER, Low-Loss α -Si:H, and Hybrid ALD Structural Resin)

Junsuk Rho (POSTECH, Korea)